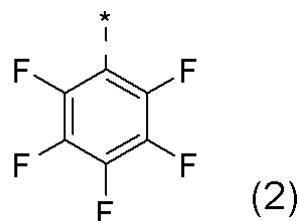
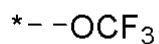
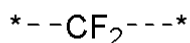
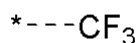
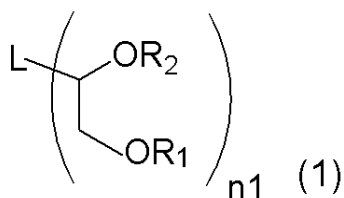


TITLE OF INVENTION: COMPOSITION FOR FORMING ORGANIC  
FILM, METHOD FOR FORMING ORGANIC FILM, AND PATTERNING  
PROCESS

ABSTRACT

A composition for forming an organic film, containing: a resin or compound; a fluorine-containing compound represented by formula (1); and a solvent, where L represents a single bond or an n1-valent organic group having 1 to 50 carbon atoms, R<sub>1</sub> represents a saturated or unsaturated monovalent organic group having 1 to 20 carbon atoms, the organic group R<sub>1</sub> having at least one fluorine-containing structure represented by any of the following formulae (2), and "\*" represents an attachment point in the organic group represented by the R<sub>1</sub>, the organic group R<sub>1</sub> optionally having two or more kinds among the structures represented by the formulae (2), or optionally having two or more identical structures. The composition has excellent in film-formability, filling property, hump suppression at the time of an EBR process and makes it possible to form an organic film having excellent process margin when used for a multilayer resist.



[FIG. 1(A)-1(F)]